

Developers

PMMA and Copolymer Resists

A Range of developers can be used with PMMA, these are typically a varying mixture of MIBK and IPA depending on what resolution and throughput is required. We can also supply a developer based on IPA:water. It has been found to improve sensitivity, contrast and exposure latitude when compared to MIBK:IPA mixtures. ^[1]

Product	Composition	Resolution	Sensitivity/Throughput
PMMA-Dev1	1:1 MIBK/IPA	Medium	High
PMMA-Dev2	1:2 MIBK/IPA	High	Medium
PMMA-Dev3	1:3 MIBK/IPA	Very High	Low
PMMA-Dev4	MIBK Pure	Low	High
PMMA-Dev7	3:7 Water/IPA	Very High	Very High

HSQ Resist

HSQ resist can be developed using a range of solvents depending on your application and requirements. The available developers are listed below.

Product	Composition	Resolution	Sensitivity/Throughput
TMAH 2.38%	TMAH/H ₂ O	Medium	High
TMAH 25%	TMAH/H ₂ O	High	Medium
Sodium Based Developer	1% NaOH/4% NaCl	High	Medium/High

GM Series Resist (SU-8)

VSLI grade PGMEA is available as a developer for GM Series (SU-8) photoresist.

All our developers and removers can be supplied in multiples of 1 litre. If there is a specific developer or remover that you require, please inquire.

1. Shazia Yasin, et al., 'Comparison of MIBK/IPA and water/IPA as PMMA developers for electron beam lithography', Microelectron, Eng, July 2002.